|            | Hits | Search Text  | DBs   |
|------------|------|--|---|
|            | птсь |  | DDS   |
| <b>6</b> 8 | 10   |  | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 69         |      | expos\$4) same voltage) and ((photoresist or resist) same  | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 70         | 50   | beam) or (sputter near9 etch\$4)) same (resist or photoresist or BARC or (organic near9 BARC) or   | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 71         |      | (((ion near9 beam) or ion) same (ash\$4 or harden\$4 or (sputter\$4 near16 beam) or (sputter near9 etch\$4) or imping\$4 or irradiat\$4 or bombard\$5) same (resist or photoresist or BARC or (organic near9 BARC) or (organic near9 | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |

|    | Hits | Search Text   | DBs   |
|----|------|---|---|
| 72 | 695  | S75 NOT S74   | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 73 | 11   | same pattern same ((etch near4 resist\$5) or harden\$5 or cured)  | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 74 |      | same (resist or photoresist or<br>BARC or (organic near9 BARC) or |   |